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Jianping Zhao is a Member of Technical Staff in Tokyo Electron. As a project manager, he is leading VHF based plasma source development including fundamental understanding on VHF related plasma physics and chemistry as well as plasma-surface interactions. He was a project manager leading various microwave plasma source development for FEOL etch applications (RLSA™) and microwave plasma CVD and ALD applications. He invented several plasma hardware that are widely used in production at major IC makers that helps TEL winning business breakthrough in FEOL market. His research, for the first time, differentiated microwave plasma and ICP. He also held several academic positions including research associate professor, STA Fellow, visiting professor in universities and national labs. Jianping holds 138 U.S. and world patents. He has 73 journal publications including Physical Review B and several invited review papers that have been cited more than 800 times. He has given many invited talks and his research has been highlighted on newspaper and magazine. He has served as a peer review for 6 journals for more than 20 years. He served as a standing committee member and session chair in dry & wet etch and cleaning symposium, CSTIC. Jianping received a Ph.D. in materials physics in 1997 with an Extraordinary Presidential Award.